J.S. De	partment	of Commerce, Pa	tent and Tradem	ark Office	Docket	Docket No. Serial N			
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1	A2	4,389,973	06/28/83	Suntola et al.	118	725	12/11/1	981	
	A3	4,413,022	11/01/83	Suntola et al.	427	255.2	06/21/1	979	
	A4	4,486,487	12/04/84	Skarp	428	216	04/25/1	983	
	A5	4,767,494	08/30/88	Kobayashi et al.	156	606	09/19/1	986	
	A6	4,806,321	02/21/89	Nishizawa et al.	422	245	07/21/1	985	
	A7	4,829,022	05/09/89	Kobayashi et al.	. 437	107	12/09/1	986	
1	A8	4,834,831	05/30/89	Nishizawa et al.	156	611	09/04/1	987	
	A9	4,838,983	06/13/89	Schumaker et al.	156	613	03/18/1	988	
	A10	4,838,993	06/13/89	Aoki et al.	156	643	12/03/1	987	
	A11	4,840,921	06/20/89	Matsumoto	437	89	06/30/1	988	
	A12	4,845,049	07/04/89	Sunakawa	437	81	03/28/1	988	
TMIT	A13	4,859,625	08/22/89	Nishizawa et al.	437	81	11/20/1	987	
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1	B4	01/29893 A1	04/26/2001	wo	H01L	21/768	<u> </u>	X	
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<u>'</u>	- C2		: Layer Deposition o etters, 6(3&4) (1999	f SiO₂ Using Catalyze), pp. 435-448.	a and Unca	talyzed Self-L	imiting Surface	Heaction:	
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1	A15	4,861,417	08/29/89	Mochizuki et al.	156	610	03/24/19	88
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	A17	4,927,670	05/22/1990	Erbil	427	255.3	06/22/19	88
	A18	4,931,132	06/05/90	Aspnes et al.	156	601	10/07/19	88
	A19	4,960,720	10/02/90	Shimbo	437	105	08/24/19	987
	A20	4,975,252	12/04/90	Nishizawa et al.	422	245	05/26/19	989
	A21	4,993,357	02/19/91	Scholz	118	715	12/21/19	989
	A22	5,013,683	05/07/91	Petroff et al.	437	110	01/23/19	89
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	A26	5,130,269	07/14/92	Kitahara et al.	437	111	04/25/19	89
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	A30	5,250,148	10/05/93	Nishizawa et al	. 156	611	11/12/	1991
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	A33	5,270,247	12/14/93	Sakuma et al.	437	133	07/08/	1992
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TNIT	A41	5,316,615	05/31/94	Copel	117	95	03/09/19	993
1	A42	5,316,793	05/31/94	Wallace et al.	427	248.1	07/27/19	992
	A43	5,330,610	07/19/94	Eres et al.	117	86	05/28/19	993
1	A44	5,336,324	08/09/94	Stall et al.	118	719	12/04/19	991
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	A47	5,374,570	12/20/94	Nasu et al.	437	40	08/19/19	993
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1	B14	00/16377 A2	03/23/2000	wo	H01L			X
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TMT	A55	5,458,084	10/17/95	Thorne et al.	117	89	12/09/19	993
1	A56	5,469,806	11/28/95	Mochizuki et al.	117	97	08/20/19	993
	A57	5,480,818	01/02/96	Matsumoto et al.	437	40	02/09/19	993
	A58	5,483,919	01/16/96	Yokoyama et al.	117	89	08/17/19	994
	A59	5,484,664	01/16/96	Kitahara et al.	428	641	01/21/19	994
	A60	5,503,875	04/02/96	Imai et al.	427	255.3	03/17/19	994
	A61	5,521,126	05/28/96	Okamura et al.	437	235	06/22/19	994
	A62	5,527,733	06/18/96	Nishizawa et al.	437	160	02/18/19	994
	A63	5,532,511	07/02/96	Nishizawa et al.	257	627	03/23/19	995
.	A64	5,540,783	07/30/96	Eres et al.	118	725	05/26/19	994
	A65	5,601,651	02/11/97	Watabe	118	715	12/14/19	994
	A66	5,616,181	04/01/97	Yamamoto et al.	118	723 ER	11/21/19	95
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TMT	A68	5,641,984	06/24/97	Aftergut et al.	257	433	08/19/19	994
1	A69	5,644,128	07/01/97	Wollnik et al.	250	251	08/25/19	994
	A70	5,693,139	12/02/97	Nishizawa et a	al. 117	89	06/15/19	993
	A71	5,705,224	01/06/98	Murota et al.	427	248.1	01/31/19	995
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	A73	5,711,811	01/27/98	Suntola et al.	118	711	11/28/19	995
	A74	5,730,802	03/24/98	Ishizumi et al.	118	719	12/27/19	996
	A75	5,747,113	05/05/98	Tsai	427	255.5	07/29/19	996
	A76	5,749,974	05/12/98	Habuka et al.	118	725	07/13/19	995
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77	11	C11			ic-Layer Deposition of Physics, Vol 75(1			le Films", <i>Ap</i>	pplied
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1	A95	6,042,652	03/28/00	Hyun et al.	118	719	09/07/	1999
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	A99	6,130,147	10/10/00	Major et al.	438	604	03/18/	1997
	A100	6,139,700	10/31/00	Kang et al.	204	192.17	09/30/	1998
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